



## Particle-free LPCVD System



### Special Features

- LPCVD system for R&D and small scale production
- Water-cooled LPCVD system  
( outside temperature of chamber: controllable under room temp.)
- Applications  
Nonotube process
- Wafer capacity  
1X4"
- Average throughput  
Up to 5,000 wafers per year
- Dimension  
1200Lx850Hx700W (mm<sup>3</sup>)
- Others  
Power: AC 20kW (3 phase, 220V)  
Pump: rotary(600l/min)  
Heating zone :  $\varphi 150 \times 160$ L (mm<sup>2</sup>)  
Heater : halogen lamp  
(max. temp.: 900°C, temp. deviation : negligible)